## Claim Amendments

Please amend claims 1, 4, 6, and 16 as follows: Please add new claims 17 and 18 as follows:

## Listing of Claims

1. (currently amended) A method for fabricating an inductor structure with an enhanced Q value comprising:

providing a substrate;

forming over the substrate a planar spiral conductor layer comprising a single spiral to form a planar spiral inductor, wherein a successive series of loops within the planar spiral conductor layer is formed with a progressive and discontinuous variation in progressing from a center of said spiral defined by a first loop to a periphery of said series of loops at least one of:

- a series of progressive stepwise changes in linewidths to form a series of discrete linewidths of for the successive series of loops; and
- a series of progressive stepwise changes in spacings separating the successive series of loops.
- 2. 3. (canceled)
- 4. (currently amended) A method for fabricating an inductor structure with an enhanced Q value comprising:

providing a substrate;

forming over the substrate a planar spiral conductor layer to form a planar spiral inductor, wherein a successive series of loops within the planar spiral conductor layer is formed with a progressive and discontinuous variation in progressing in any direction from a center of said spiral defined by a first loop to a periphery of said series of loops at least one of:

a series of progressive stepwise changes in linewidths to form a series of discrete linewidths of for the successive series of loops; and

a series of <u>progressive stepwise changes in spacings</u> separating the successive series of loops:

wherein the successive series of loops is formed in a shape selected from the group consisting of a triangle, a square, a rectangle, a higher order polygon, a uniform ellipse and a circle.

5. (original) The method of claim 1 wherein the planar spiral conductor layer is formed of a conductor material selected from the group consisting of non-magnetic metal, non-magnetic metal alloy, magnetic metal, magnetic metal alloy, doped polysilicon and polycide conductor materials, and laminates thereof.

- 6. (currently amended) The method of claim 1 wherein the variation in the series of linewidths of the successive series of loops is an increasing progression of linewidth progressive stepwise changes to form a series of discrete linewidths increases from [[a]] the first loop which defines the center of the planar spiral inductor having a comparatively narrow linewidth to a final loop which defines the perimeter of the planar spiral inductor having a comparatively wide linewidth.
- 7. (original) The method of claim 6 wherein the comparatively narrow linewidth is from about 7 to about 10 microns and the comparatively wide line width is from about 17 to about 21 microns.
- 8. (currently amended) The method of claim 1 wherein the successive <u>series of</u> loops <del>of spirals</del> <u>comprising the single spiral</u> comprises from about 1 to about 8 loops.
- 9. 15. (canceled)
- 16. (currently amended) The method of claim 1 wherein the progressive and discontinuous variation is a comprises progressively increasing or decreasing stepwise changes discontinuous variation.
- 17. (new) The method of claim 1, wherein the successive series of loops is formed in a shape selected from the group consisting of

a triangle, a square, a rectangle, a higher order polygon, a uniform ellipse and a circle.

18. (new) The method of claim 4 wherein the progressive stepwise changes to form a series of discrete linewidths increases from a first loop which defines the center of the planar spiral inductor having a comparatively narrow linewidth to a final loop which defines the perimeter of the planar spiral inductor having a comparatively wide linewidth.